Timetable

CT: Contributed Talk, IT: Invited Talk.

Thursday, December 12th

8:30-8:55	Registration		
8:55-9:00	Welcome remarks		
9:00-9:50	IT	T. Minea	Plasma behavior in pulsed magnetrons
7.00-7.50	11	Université Paris-Saclay	and new trends for plasma excitation
9:50-10:20	Coffee break		
Session:	Microstructural and textural control		
10:20-11:10	IT	N. Martin	Structuring of thin films combining
10.20-11.10	11	FEMTO-ST	reactive gas pulsing and GLAD
		J. Müller	In silico optimization of reactively
11:10-11:30	CT	University of Namur	sputtered meso-porous titanate-based
			thin films by genetic algorithm
			Real-time growth monitoring of
11:30-11:50	СТ	K. Solanki	ultrathin Ag layers: impact of N ₂
11.50 11.50	Ci	Université de Poitiers	additives and seed layers on
			morphological evolution
		T. Suszko	MeMC/a-C:H type coatings with
11:50-12:10	CT	Koszalin University of	nanocolumnar, composite structure-
		Technology	synthesis and some properties
12:10-12:40	Presentation of the posters (first group)		
12:40-13:50	Lunch		
13:50-14:20	Presentation of the posters (second group)		
	СТ	S. Frick	Accelerating oxynitride coating
14:20-14:40		EMPA	development: Combinatorial
			investigation on the Al-Si-O-N system
14:40-15:00	СТ	F. Farahani Ghent University	Do impurities have an influence on the
			phase composition of deposited
			tungsten films?

Session:	Emerging techniques for reactive sputtering		
15:00-15:50	IT	A. Shukurov Charles University	Reactive sputter-driven synthesis of transition metal nanoparticles and nanofluids
15:50-16:20	Coffee break		
16:20-16:40	СТ	P. Baroch University of West-Bohemia	High-rate reactively sputtered Cu₂O thin films post-treated with high-power infrared laser
16:40-17:00	СТ	C. Schiffers CemeCon AG	HiPIMS coatings for sub-micro tools for AI applications
17:00-17:20	СТ	P. Vašina Masaryk University	Exploring different models of operation of multipulse HiPIMS
20:00-22:30	Conference dinner		

Session:	Poster presentations I		
12:10-12:15	Р	D. Loch	Silicon Dioxide Coatings by Reverse
		Trumpf Hüttinger GmbH	Pulse HIPIMS
			Real-time in-situ sheet resistance
12:15-12:20	Р	A. Debrabandere	measurements to study silver thin film
12.13 12.20		Ghent University	nucleation during magnetron
			sputtering
			Exploring Engineered Artificial Minerals
12:20-12:25	Р	F. Lourens	for Lithium Recovery from Recycling
		Ruhr University Bochum	Slags: Insights from Thin Film
			Experiments
		J. Müller	Reactive Superimposed HiPIMS / RF
12:25-12:30	Р	Fraunhofer Institute for	Deposition
		Mechanics of Materials	·
12:30-12:35	Р	N. Rodkey Empa	Accurate Reporting of Time-of-Flight
			Measurements with Gated Mass
			Spectrometry
12:35-12:40	Р	M. Aelbrecht Soleras Advanced Coatings	New thermal spray ceramic NiOx(CrOx)
			targets for sputtering functional layers
			in low-E glass coatings

Session:	Poster presentations II		
13:50-13:55	Р	P. Marx Ruhr University Bochum	Combinatorial Sputter Synthesis and Characterization of (La-)Co-based Thin-Film Spinel and Perovskite Materials Libraries
13:55-14:00	Р	E. Dobruchowska Koszalin University of Technology	NiMo-C coatings synthesised by reactive magnetron sputtering as a catalyst for the hydrogen evolution reaction in an acidic environment
14:05-14:10	Р	E. Strods University of Latvia	Optical and photochromic properties of yttrium oxyhydride thin films deposited by reactive magnetron sputtering
, 14:10-14:15	Р	A. le Febvrier Luleå University of Technology	Embedding Fe Nanoparticles into CrN Films For enhancing thermoelectric properties
14:15-14:20	Р	O. Brune Technical University of Munich	Enhancing Charge Transport in Metal (Oxy-)Nitrides for Efficient Solar Fuel Generation

Friday, December 13th

Session:			s and process control
9:00-9:50	IT	P. Eklund	Thin film ceramics for Energy
		Uppsala University	Applications
		L.I. Wagner	Engineering Ti-doped Ta₃N₅
9:50-10:10	СТ	Technical University of	Photoanodes via Reactive Magnetron
7.50 10.10	Ci	Munich	Co-Sputtering for Enhanced Solar Fuel
		Marien	Applications
		T. Kubart Uppsala University	Superconducting NbN thin films
10:10-10:30	СТ		deposited by reactive magnetron
			sputtering
10:30-11:00		Coff	ee break
		L. Maroto-Diaz	The study of defect reduction in optical
11:00-11:20	СТ	Gencoa Ltd.	coatings produced using reactive
			process feedback control
11:20-11:40	СТ	J. Van Bever	How to converge feedback control and
		Ghent University	measure double hysteresis?
		K. Choglay	Exploring the Link between Plasma Gas
11:40-12:00	СТ	Manchester Metropolitan	Speciation and the properties of TiO _x N _y
		University	Thin Films
12:00-13:15		Lunch	
Session:	Smart sensing and complex coatings		-
13:15-14:05	IT	F. Vaz	Specially architectured thin films for
10.15 14.05		University Minho	sensing applications
		A. Crovetto	Phosphide and phosphosulfide thin
14:05-15:25	СТ	Technical University of	films by reactive sputtering
		Denmark	
15:25-15:45	СТ	P. Kelly Manchester Metropolitan University	Deposition of BiVO ₄ Thin Films by
			Reactive Magnetron Co-Sputtering for
			Visible Light Photoelectrochemical
		•	Water Splitting
15:45-16:05	СТ	D. Depla	The future of RSD and reactive
		Ghent University	sputtering
16:05-16:30	Closing ceremony		